EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L5	236	((wafer or substrate or semiconductor) near5 (wash$4 or clean$4 or decontaminat$4 or etch$4 or remov$4)) AND ((FOAM OR BUBBLE OR SUDS OR FROTH OR LATHER) NEAR2 (NOZZLE OR APPLICATOR OR SPRAY$4 OR SPOUT OR DISTRIBUTOR)) AND ((NOZZLE OR APPLICATOR OR SPRAY$4 OR SPOUT OR DISTRIBUTOR) NEAR2 (MOVABLE OR MOVES OR MOVING OR TRANSLATE OR AMBULATORY OR ADVANC$4 OR SCAN$4 OR DISPLAC$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/10 08:32
L6	192	((wafer or substrate or semiconductor) near2 (wash$4 or clean$4 or decontaminat$4 or etch$4 or remov$4)) AND ((FOAM OR BUBBLE OR SUDS OR FROTH OR LATHER) NEAR2 (NOZZLE OR APPLICATOR OR SPRAY$4 OR SPOUT OR DISTRIBUTOR)) AND ((NOZZLE OR APPLICATOR OR SPRAY$4 OR SPOUT OR DISTRIBUTOR) NEAR2 (MOVABLE OR MOVES OR MOVING OR TRANSLATE OR AMBULATORY OR ADVANC$4 OR SCAN$4 OR DISPLAC$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/10 08:37